CLAIMS

1. A physical vapor deposition (PVD) chamber, comprising a chamber body, an upper electrode assembly being arranged in the chamber body, and the upper electrode assembly including a base plate assembly configured to carry a magnetron, a backplate superimposed at an interval with the base plate assembly, and a connection assembly for connecting the base plate assembly to the backplate, the backplate being arranged at a side of the base plate assembly away from the magnetron;

wherein, the connection assembly includes a connection bolt, a bolt head of the connection bolt is connected to the base plate assembly, and a bolt of the connection bolt is threadedly connected to the backplate.

2. The PVD chamber according to claim 1, wherein a plurality of connection assemblies are included, and the plurality of connection assemblies are staggered with the magnetron and are arranged at intervals.

3. The PVD chamber according to claim 2, wherein the bolt head of the connection bolt is rotatably connected to the base plate assembly.

4. The PVD chamber according to claim 3, wherein:

the bolt head of the connection bolt is configured to have a convex spherical surface; and

a spherical seat cooperating with the convex spherical surface is provided on the base plate assembly.

5. The PVD chamber according to claim 4, wherein:

the base plate assembly includes a base plate body, the base plate body is provided with the spherical seat and a through hole communicated with the spherical seat, the convex spherical surface of the connection bolt fits in the spherical seat, and the bolt extends from the through hole, a diameter of the convex spherical surface being greater than a diameter of the through hole.

6. The PVD chamber according to claim 5, wherein the base plate assembly further includes a fixing module having a concave spherical surface cooperating with the convex spherical surface, the fixing module is fixed on the base plate body, and the concave spherical surface fits with the convex spherical surface .

7. The PVD chamber according to claim 6, wherein a recess is formed at the base plate body, the spherical seat is formed on a bottom surface of the recess, the fixing module is embedded in the recess, and a surface of the fixing module is flush with a surface of the base plate body.

8. The PVD chamber according to claim 6 or 7, wherein an operation hole leading to the convex spherical surface is provided at the fixing module, and an operation groove corresponding to the operation hole is provided at the convex spherical surface.

9. The PVD chamber according to claim 8, wherein the fixing module is fixedly connected with the base plate body through a screw.

10. A physical vapor deposition (PVD) apparatus, comprising the PVD chamber according to any one of claims 1 to 9.